

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	103	(gustaaf.in. near5 feltz.in.) (cheng-qun.in. near2 gui. in.) (johan.in. near4 hoefnagels.in.)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/27 16:22
L3	29167	((substrate wafer) near4 (temperature heat\$3)) with (measur\$5 sens\$3 detect\$3 determin\$5)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/27 16:23
L4	37116	((substrate wafer) with ((dimension\$3 near response) expan\$4 deform \$5 (spatial near distribution)) with (calculat \$3 determin\$5 predict\$3 model\$3 coefficient co efficient measur\$5)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/27 16:54
L5	1	2 and (3 and 4).clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/27 17:36
L6	1	2 and (3).clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/27 17:36
L7	2061	(3 and 4)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/27 17:36
L8	4239	3 with (area region portion section)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/27 17:39

L9	328	8 and 4	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/27 17:39
L10	2789019	(different first second) near6 (area region portion section)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/27 17:41
L11	161933	(different first second) near6 (area region portion section) near5 (substrate wafer)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/27 17:41
L12	120	9 and 11	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/27 17:42
L13	81	@ad<="20040329" and 12	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/27 17:42
L14	4190739	(pattern\$3 form\$3 expos\$5 record\$3 project\$3) with (pattern image mark circuit)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/27 17:46
L15	189557	(pattern\$3 form\$3 expos\$5 record\$3 project\$3) near5 (pattern image mark) near5 (substrate wafer)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/27 17:47
L16	27	13 and 15	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/27 17:48
L17	7	(3 and 4 and 15).dm.	US-PGPUB	OR	ON	2008/03/27 18:00

L18	90217	(shape cross\$section\$3 size location position disposition disposed) near3 (beam light radiation illumination) with (correct\$3 adjust\$4 compensat\$3 chang\$3)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/27 18:21
L19	70	3 and 4 and 18	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/27 18:22
L20	21	8 and 4 and 18	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/03/27 18:23
L21	1	(8 and 4 and 18).dlm.	US-PGPUB	OR	ON	2008/03/27 18:23

3/27/2008 6:23:59 PM

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